

Supplemental Information

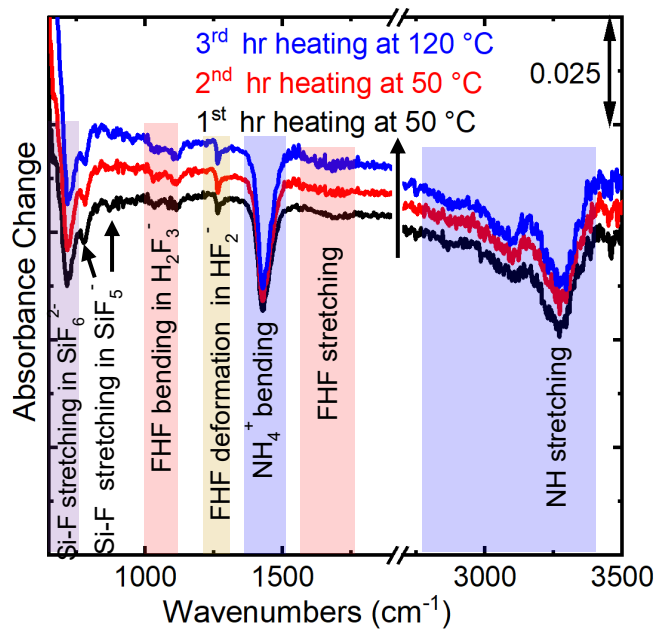


Figure 1: Change in absorbance after thermal treatment of the salt layer formed during etching of SiN_x in HF plasma. The reference spectrum was collected prior to thermal treatment.